No. of Printed Pages : 2

**BIELE-007** 

## B.Tech. – VIEP – ELECTRONICS AND COMMUNICATION ENGINEERING (BTECVI)

## **Term-End Examination**

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## **June, 2018**

## **BIELE-007 : NANO-ELECTRONICS**

Time :	3 hours			Maximum Marks : 70					
Note :	Attem	pt any <b>s</b>	e <b>ven</b> ques	tions. All	questie	ons	carry		
	-		Assume	missing	data,	if	any,		
	suitably.								

1.	Expla	Explain various scaling effects on MOSFET. 1			10			
2.	Discuss the concept of : 5-					5+5		
	(a)	Cha	arge	quantizatio	n			
	(b)	Ene	ergy	quantizatio	n			
3.		_		gram explai teristics.	n Si-Ge h	eterostruc	ture	10
4.	What Spin-2			difference	between	CNFET	and	10
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5.	Explain the working principle of the following with neat diagram :5+5(a) FinFET5(b) Vertical MOSFET5
6.	Explain various challenges in sub-100 nm technology. 10
7.	WhatisSilicon-on-nothingandSilicon-on-insulator ? Differentiate them.10
8.	With help of diagram, explain the working ofresonant-tunneling diode. State its use.10
9.	Draw the input-output characteristics of10(a)Enhancement type MOSFET(b)NPN transistor in common collector configuration.
10.	Draw the energy band structure of the following : 5+5 (a) II - VI compounds

(b) Type – III heterojunctions